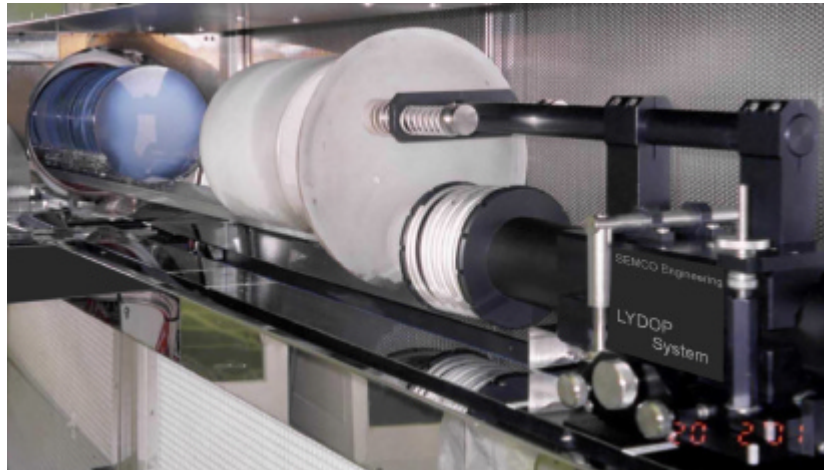


# LYDOP<sup>®</sup>

## Unique Phosphorous and Boron Doping system

The LYDOP<sup>®</sup> is a reduced pressure process system and cantilever which meets semiconductor manufacturers' demand for higher throughput, better uniformity and maximized uptime.



### Features

- Combines the best features of atmospheric, LPCVD and MOCVD process
- Includes reactor tube, gas system, pump system, cantilever and door closure
- Adaptable to any brand of furnace
- Available for up to 200 mm wafers
- Liquid or gas source compatible
- Suitable for automated furnace loading

### Advantages

- ◆ Downtime reduced to 5% : tube maintenance once a year only !
- ◆ 33% reduction in chemical consumption
- ◆ Capacity increased up to 200 wafers per run
- ◆ Outstanding Rs uniformity results : typ. 1%
- ◆ Unequaled repeatability of the process
- ◆ Environment friendly : drastically reduced POCl<sub>3</sub> vapor emission and chemical consumes